



First Call For Papers

THE 65TH SYMPOSIUM ON SEMICONDUCTORS AND INTEGRATED CIRCUITS TECHNOLOGY

Kikai-Shinko Kaikan
Tokyo, Japan
December 18-19, 2003

Organized by:
Electronic Materials Committee,
The Electrochemical Society of Japan.

The 65th Symposium on Semiconductors and Integrated Circuits Technology will be held on December 18-19, 2003 in Tokyo, Japan. This symposium brings together scientists and engineers to discuss advances in the field of semiconductors and integrated circuits technology. The official languages of the symposium are Japanese and English. A proceedings volume will be published. Papers are solicited on "High Performance Si Devices" and "Advanced Copper and Low-k Interconnect Technology".

Kikai-Shinko Kaikan, Tokyo
3-5-8, Shiba Park, Minato-ku,
Tokyo, Japan 105
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Papers are solicited on "High Performance Si Devices" and "Advanced Copper and Low-k Interconnect Technology". The focused sessions and the list of invited speakers are as follows.

< High Performance Si Devices >

- 1.High Performance Strained-SOICMOS Technology
T. Mizuno (*MIRAI-ASET*)
- 2.Improvement in Performance of Transistors for Next Technology Node Logic LSIs
K. Suguro (*Toshiba Semiconductor*)
3. Silicon oxynitride gate dielectrics for advanced CMOS devices
J. Yugami (*Renesas Technology*)
- 4.Shallow Junction Technology
(*to be announced*)

< New Integration Technology and Systems >

1. Three-Dimensional Integration Technology and New Integrated Systems
M. Koyanagi (*Tohoku Univ.*)

<Advanced Cu & low-k interconnect technology>

1. Fluid-Metallization using Supercritical Fluids
E. Kondoh (*Yamanashi Univ*)
- 2.Cleaning Technologies for Cu/Low-k Interconnection
H. Aoki (*NEC Electronics*)
3. A Highly Reliable Cu/VLK(k<2.3) Multilevel Interconnects for SoC Technologies on 65nm Node and Beyond
I. Sugiura (*Fujitsu Laboratories*)

Related papers are strongly requested.

The deadline of the abstract submission is **Sep.24,2003**. A 75-word abstract along with title, the authors' names, affiliation, address, telephone, fax number and e-mail address should be sent to:

Secretariat, Electronic Materials Committee,
The Electrochemical Society of Japan,
Arusu Ichigaya 202, 4-8-30, Kudan-minami,
Chiyoda-ku, Tokyo 102-0074, Japan
(Tel.81-3-3234-4213, Fax.81-3-3234-3599)
E-mail : ohnishi@electrochem.jp

Authors must submit their camera-ready manuscripts for the proceedings by **Nov. 25**.

Symposium Chair: Shunri Oda
(*Tokyo Inst. of Technol.*)
Program Chair: S.Shima
Session Chairs: A. Hashimoto, K. Kobayashi
M. Moniwa, R. Nakata, H. Suzuki

Electronic Materials Committee

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M. Yamaguchi (*Kaneka*)
M. Yoshimaru (*Oki Electric Industry*)
Overseas Member:
M.Yoshida (*Samsung*)

— Traffic to Kikai-Shinko Kaikan. Tokyo —
Subway: 7min. on foot from Kamiyacho Station
(Hibiya line), 7min. on foot from Onarimon Station
(Toei Mita line)
JR: 10min. On foot from Hamamatsucho Station
Hotel
A: Shiba Park Hotel Tel.+81-3-3433-4141
B: Tokyo Prince Hotel Tel.+81-3-3432-1111